

Title (en)  
SUBSTRATE HOLDER FOR USE IN A LITHOGRAPHIC APPARATUS AND A METHOD OF MANUFACTURING A SUBSTRATE HOLDER

Title (de)  
SUBSTRATHALTER ZUR VERWENDUNG IN EINEM LITHOGRAPHISCHEN GERÄT UND VERFAHREN ZUR HERSTELLUNG EINES SUBSTRATHALTERS

Title (fr)  
SUPPORT DE SUBSTRAT DESTINÉ À ÊTRE UTILISÉ DANS UN APPAREIL LITHOGRAPHIQUE ET PROCÉDÉ DE FABRICATION D'UN SUPPORT DE SUBSTRAT

Publication  
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Application  
**EP 21729829 A 20210525**

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Abstract (en)  
[origin: WO2021249768A1] Described herein is a method of producing a substrate holder for use in a lithographic apparatus, the substrate holder comprising a plurality of burls projecting from the substrate holder and each burl having a distal end surface configured to engage with a substrate. The method including applying, via a plasma enhanced chemical vapor deposition, a coating of a wear-resistant material at the distal end surface of one or more burls of the plurality of burls. The applying of the coating includes adjusting radio frequency (RF) power of RF electrodes in a range 100 to 1000 W for creating plasma; and exposing, in a chamber, the one or more plurality of burls to a precursor gas at a gas flow rate between 20 to 300 seem, the pre-cursor gas being Flexane.

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